

INFORMATION DISCLOSURE STATEMENT

Applicant : Masuda et al.
App. No : 10/568,126
Filed : February 14, 2006
For : POSITIVE PHOTORESIST
COMPOSITION AND RESIST PATTERN
FORMATION
Examiner : Chu, John S Y
Art Unit : 1795

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 5 (five) references to be considered by the Examiner. Also enclosed are 3 (three) foreign patent references and/or non-patent literature as listed on the Information Disclosure Statement.

This Information Disclosure Statement is being filed after the mailing date of a final action or after the mailing date of a Notice of Allowance. This Statement is accompanied by the fee set forth in 37 C.F.R. § 1.17(p). The Commissioner is hereby authorized to charge any additional fees which may be required or to credit any overpayment to Account No. 11-1410.

CERTIFICATION UNDER 37 C.F.R. § 1.97(e)(1)

I hereby certify that each item of information contained in this Statement was first cited in any communication from a foreign Patent Office in a counterpart foreign application not more than three months prior to the filing of this Information Disclosure Statement.

Respectfully submitted,
KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 6/25/09

By: 

Neil S. Bartfeld, Ph.D.
Registration No. 39,901
Agent of Record
Customer No. 20,995
(619) 235-8550